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 APPLICANT SHIMADA et al
 FILING DATE February 4, 2004 GROUP 2871

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

DOCUMENT	DATE	COUNTRY	TRANSLATION		
			CLASS	SUBCLASS	YES NO
0 486 047	5-1992	EP			
6-346025 A	12-1994	JP			partial

OTHER DOCUMENTS (including Author, Title, Date, Pertinent pages, etc.)

	Stanley Wolf et al., Silicon Processing For The VLSI Era, vol. 1, Process Technology, Lattice Press, Sunset Beach, CA., 1986.
	Tadanori Shimoto et al. High Density Multilayer Substrate Using Benzocyclobutene Dielectric, IMC 1992 Proceedings, Yokohama, Jun. 35-5, 1992, pp: 3255-330.
	Willem den Boer et al., High Aperture TFT LCD using Polymer Interlevel Dielectric, OIS Optical Imaging Systems, Inc., Northville, MI, USA.
	M.J. Radler et al., Cyclotene.TM. Advanced Electronics Resins for High5-Aperture AMLCD Applications, SID 96 Applications Digest, pp. 335-36 (1996).
	Eric P. Finchem et al., A Multi5-Level High Density Interconnect Process Designed & Developed for Manufacturability, TriQuint Semiconductor, Inc., Beaverton, OR, USA.
	M.J. Radler et al., Benzocyclobutene Dielectric Resins for Flat Panel Display Applications, Proceedings of the 3.sup.rd Annual Display Manufacturing Technology Conference, pp: 1235-124, 1996 (Conference date: Feb. 65-8, 1996).
	M.W. Friends, Determination of Dielectric Constant for Fuji Clear, Mar. 7, 1996, pp:15-2, including Table.
	Willem den Boer, A Two5-Diode Pixel Circuit and Addressing Method for MIM LCDs, OIS Optical Systems, Inc., Northville, MI, USA.
	Tech Notes, Advanced Electronics Resins, Processing Guide for Photo5-Imageable BCB, Dow Chemical Co., pp: 15-4.
	Decision on Appeal mailed October 12, 2001 in corresponding JP application No. 10-220219 (JP Patent No. 3247870)
	Notice of Reasons for Rejection mailed March 16, 2004 in corresponding JP application No. 2001-44409, which is a divisional appln. of JP 10-220220NN
	European Search Report mailed June 4, 2004 in corresponding EP application 02017257.3

*Examiner	Date Considered
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Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to application.